



Nanoimprinted and Anodized Templates for Large-Scale and Low-Cost Nanopatterning

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Table S1 collects the geometrical parameters, such as periodicity, P , linewidth, w , line height, h , and mold thickness, T , of the commercial optical disks employed as molds for the imprint step and with indication of whether single polycarbonate, PS, or polycarbonate stamp with metallic layer, PS/ML, were used.

Table S1. Geometrical parameters [1]: Polycarbonate section (Pol.): Polycarbonate stamp with metallic layer (PS/ML) or Polycarbonate stamp (PS); periodicity (P), linewidth (w), line height (h) and mold thickness (T).

Optical Disk	Pol.	P (nm)	W (nm)	h (nm)	T (mm)
CD	PS/ML	1600	600	130	0.1
CD	PS	1600	1000	130	1.1
DVD	PS/ML	740	320	65	0.6
DVD	PS	740	420	65	0.6
BR	PS/ML	320	130	40	1.1
BR	PS	320	190	40	0.1

SEM images of the PAA nanostructured templates, after a single anodization step of Al substrates and pre-patterned using a CD-PS/ML mold, are shown in Figure S1. PAAs with a single-imprint process exhibit two sets of parallel pores well aligned along the pre-patterning lines and separated by around 400 nm as well as around 800 nm width regions where the pores are randomly grown (see Figure S1 a and b). On the other hand, PAAs with a rhombic geometry also exhibit two sets of parallel pores well aligned along the pre-patterning lines, and a rhombic area with a lateral size of around 500 nm and where pores are mainly growing at the rhomboid edges (in Figure S1 c, d and e).

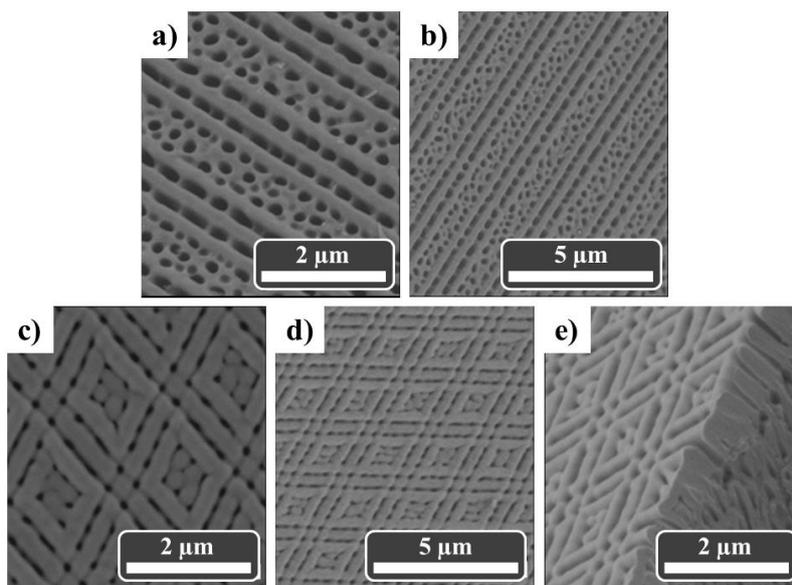


Figure S1. Top-view (a-d) and cross section (e) SEM images of PAA templates with line (a and b) and rhombic configurations (c, d and e) imprinted using CD-PS/ML molds and after a single anodization step under a constant voltage of 195 V in 0.03M H_3PO_4 acid solution at 5°C and for 2 h.

Figure S2. depicts the SEM images of PAA nanostructured templates with line (a and b), square (c and d) and triangular (e and f) geometrical configurations imprinted using DVD-PS/ML molds and a single anodization step under constant voltage of 165 V in 0.03M H_3PO_4 solution at 5°C and for 2 hours.

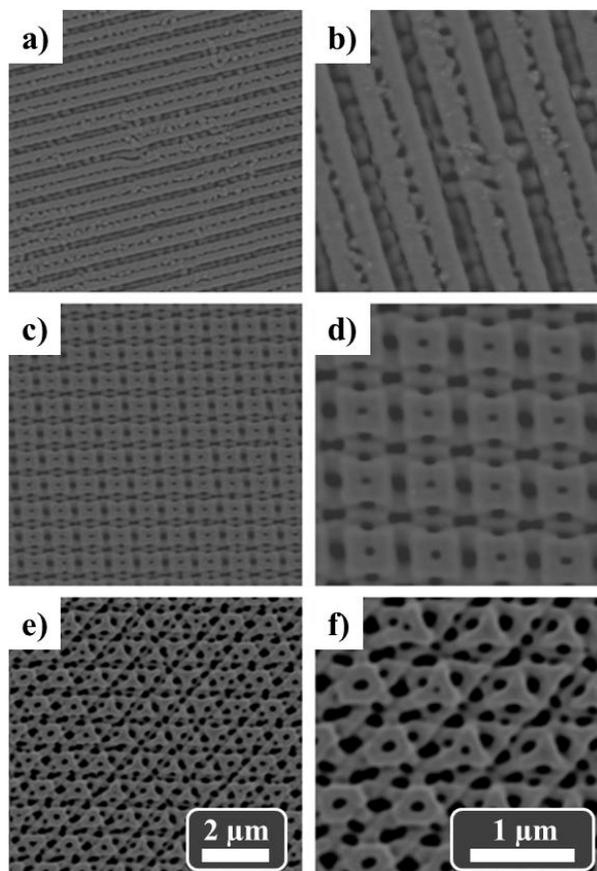


Figure S2. Top-view SEM images of PAA templates with line (a and b), square (c and d) and triangular configurations (e and f) imprinted using DVD-PS/ML molds and a single anodization step under constant voltage of 165 V in 0.03M H_3PO_4 solution at 5°C and for 2 hours.

Figure S3 shows a free-standing square Co nanostructure after the chemical dissolution of the PAA template in a solution of phosphoric and chromic acids at 50°C for 10 min.

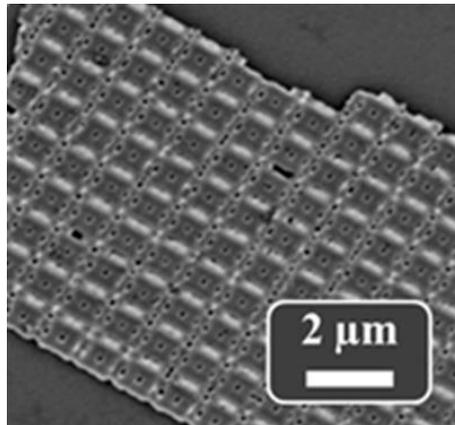


Figure S3. SEM image of a free-standing square Co-nanostructure.

Figure S4 shows the XRD patterns of the Co thin films sputtered onto the PAA templates.

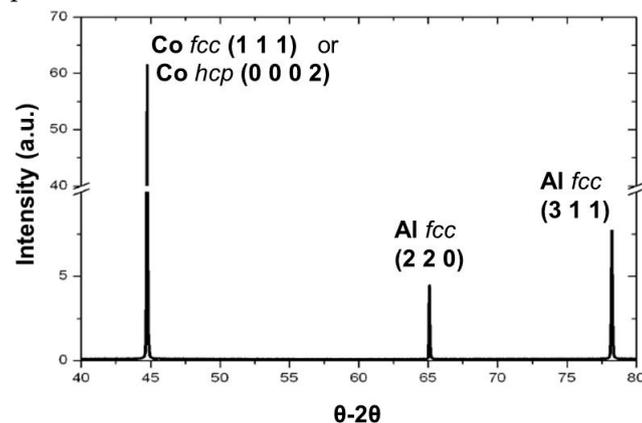


Figure S4. XRD pattern of Co nanostructures growth on PAA templates.

Figure S5 a shows the azimuthal or in-plane angular dependence of the VSM hysteresis loops for the Co nanodot array as well as its in-plane coercivity (Figure S 5b) and reduced remanence (Figure S5 c). In this analysis, the 0° orientation corresponds to the direction parallel to the side of the square dot. The hysteresis loops are clearly inclined with regards to the in-plane loops previously described for the arrays of Co nanostripes (see Figure 6 in the main text). In addition, the hysteresis loops do not show any significant evolution with the angular dependence which could be related to a less defined shape anisotropy term. A deeper analysis of the angular dependence of coercivity and remanence suggests the presence of a modest in-plane bi-axial magnetic anisotropy with magnetization easy axes at 90° to each other that can be correlated to the cubic array of squared Co nanodots.

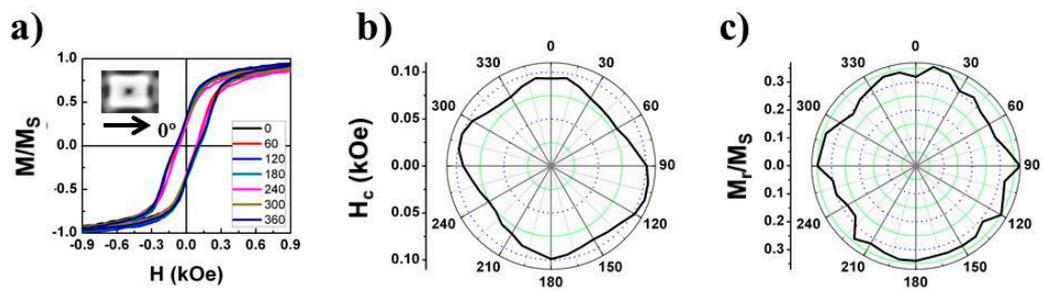


Figure S5. In-plane azimuthal VSM hysteresis loops (a) together with the corresponding dependence of coercivity, H_c , (b) and reduced remanence, M_r/M_s , (c) for a cubic array of squared Co nanodots.

References

S1. <http://osta.org/>